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(71) Applicant (for all designated States except US): ADAPTIVE PLASMA TECHNOLOGY CORPORATION [KR/KR]; 1 Yeongtong-dong, Yeongtong-gu, Suwon-si, Gyeonggi-do 443-808 (KR).

(72) Inventors; and

(75) Inventors/Applicants (for US only): KIM, Nam-hun [KR/KR]; 804-302 Byeokjeokgol Dusan Apt., 973-3 Yeongtong-dong, Paldal-gu, Suwon-si, Gyeonggi-do

442-470 (KR). LEE, Do-hyung [US/US]; 20350 Stevens Creek Blvd. #320, Cupertino, CA 95014 (US). OH, Young-kun [KR/KR]; 123-502 Daelim Apt., Haeng-dang-dong, Seongdong-gu, Seoul 133-070 (KR).

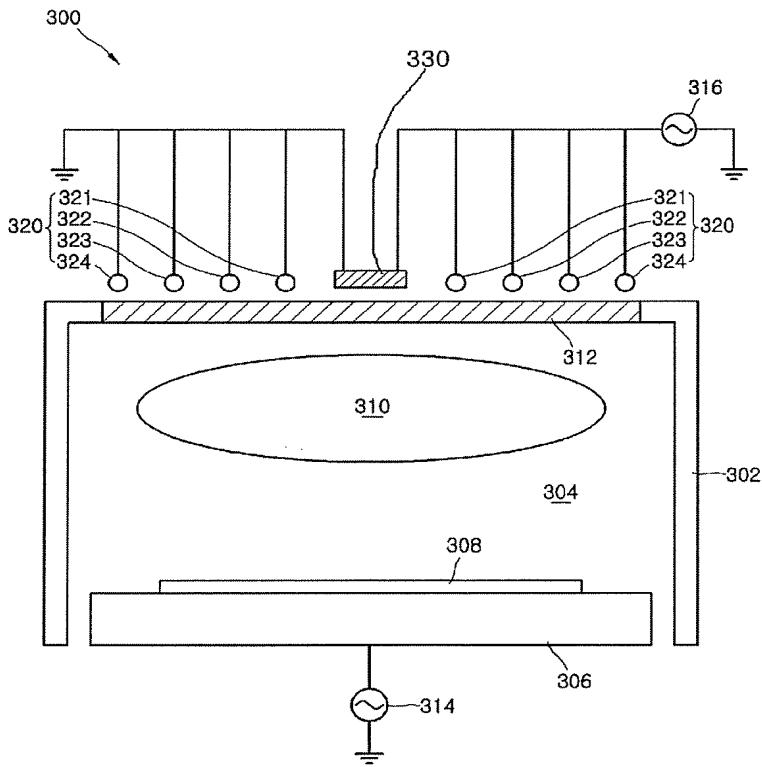
(74) Agent: AJU INTERNATIONAL LAW & PATENT GROUP; 12th Floor, Poonglim Building, 823-1 Yeoksam-dong, Kangnam-gu, Seoul 135-784 (KR).

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(54) Title: PLASMA SOURCE COIL AND PLASMA CHAMBER USING THE SAME



(57) Abstract: A plasma source coil includes a bushing arranged at a center part, and a plurality of unit coils arranged in the form of a concentric circle from a circumference of the bushing on the bases of the bushing. One end of each unit coil and one end of the bushing are commonly connected to a power-supply terminal, and the other end of each unit coil and the other end of the bushing are commonly connected to a ground terminal.

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